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IN THE CLAIMS

1-19 (canceled)

20.(currently amended)

A process comprising:

applying an aqueous, acidic solution comprising having dissolved contents to a metallic surface, said metallic surface comprising at least 5% by weight of at least one of aluminum or an aluminum alloy, wherein the dissolved contents in the phosphating solution comprise:

virtually no sodium or a concentration of sodium in the range of at least 0.04 g/l, virtually no potassium or a concentration of potassium in the range of at least 0.025 g/l, wherein the concentrations of sodium and potassium together is in the range of 0.3 to 1.8 g/l as sodium, the potassium content being converted to sodium on a molar basis; zinc in a concentration range of 0.2 to 4 g/l; phosphate in a concentration range of 4 to 65 g/l, calculated as PO₄;

free fluoride in a concentration range of 0.03 to 0.5 g/l 0.5 gl;

total fluoride in the concentration range of 0.1 to 5 g/t;

wherein no or almost no precipitation product based on <u>aluminum</u> aluminium fluorocomplexes of ammonium, alkali metal or alkaline-earth metal is deposited on said metallic surface, below the phosphate film and/or between the zinc phosphate crystals in the phosphate film on the surfaces of <u>aluminum</u> aluminium or at least one <u>aluminum</u> aluminium alloy phosphated in this way and wherein a zinc-containing phosphate film is deposited on the metallic surfaces and has a coating weight in the range of 0.5 to 10 g/m², whereby the value of the free acid KCl is kept in the range of 1.6 to 2.8.

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- 21. (currently amended) The process according to claim 20, wherein the contents of dissolved aluminum aluminium in the phosphating solution are in the concentration range of 0.002 to 1 g/l.
- 22. (previously presented) The process according to claim 20, wherein the total content of silicon complex fluoride and boron complex fluoride together in the phosphating solution is 0.01 to 8 g/l optionally converted on a molar basis as SiF₆, wherein the two groups of fluoride complexes may optionally both be present at the same time.
- 23. (previously presented) The process according to claim 20, wherein the content of complex bound fluoride in the phosphating solution is from 0.01 to 8 g/l, calculated on a molar basis as SiF₆.
- 24. (previously presented)The process according to claim 20, wherein the contents dissolved in the phosphating solution are as follows:

sodium: in the concentration range of 0.050 to 2 g/l,

potassium: virtually none or in the concentration range of 0.030 to 1.5 g/l,

sodium and potassium: in the concentration range of 0.025 to 1.5 g/l as sodium, potassium being converted to sodium on a molar basis,

silicon complex fluoride: in the concentration range of 0.01 to 4 g/l and/or

boron complex fluoride: in the concentration range of 0.01 to 4 g/l, calculated as SiF₆ and BF₄ respectively.

25. (previously presented) The process according to claim 20, wherein at least one of the contents in the phosphating solution are as follows:

sodium: virtually none or in the concentration range of 0.060 to 1.8 g/l;

potassium: in the concentration range of 0.035 to 1.4 g/l;

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sodium and potassium: in the concentration range of 0.05 to 2 g/l as sodium, potassium being converted to sodium on a molar basis;

silicon complex fluoride: in the concentration range of 0.02 to 1 g/l or

boron complex fluoride: in the concentration range of 0.02 to 3 g/l, calculated as SiF_6 and BF_4 respectively.

- 26. (previously presented) The process according to claim 20, wherein the dissolved contents comprise at least one of nickel: virtually none or in the range of 0.001 to 3 g/l or manganese: virtually none or in the range of 0.002 to 5 g/l.
- 27. (previously presented) The process according to claim 20, wherein the dissolved contents comprise at least one of

dissolved iron²⁺ ions: virtually none or in the concentration range of 0.005 to 3 g/l or complexed iron³⁺ ions: virtually none or in the concentration range of 0.005 to 1 g/l.

28. (previously presented)The process according to claim 20, wherein the dissolved contents comprises at lest one of:

silver: virtually none or in the concentration range of 0.001 to 0.080 g/l or copper: virtually none or in the concentration range of 0.001 to 0.050 g/l.

29. (previously presented) The process according to claim 20, wherein the dissolved contents comprises at least one of:

titanium: virtually none or in the concentration range of 0.001 to 0.200 g/l or zirconium: virtually none or in the concentration range of 0.001 to 0.200 g/l.

30. (previously presented) The process according to claim 20, wherein the dissolved contents comprise at least one of:

ammonium: virtually none or in the concentration range of 0.01 to 50 g/l or nitrate: virtually none or in the concentration range of 0.01 to 30 g/l.

31. (previously presented)The process according to claim 20, wherein the dissolved contents comprise at least one of:

sulfate: virtually none or in the concentration range of 0.005 to 5 g/l or chloride: virtually none or in the concentration range of 0.020 to 0.5 g/l.

32. (previously presented)The process according to claim 20, wherein the phosphating solution comprises at least one accelerator selected from the group consisting of a compounds or ions based on

nitrogen-containing compounds in the concentration range of 0.01 to 8 g/l; chlorate in the concentration range of 0.01 to 6 g/l; hydroxylamine in the concentration range of 0.01 to 3 g/l; and

peroxide, including water-soluble organic peroxide, in the concentration range of 0.001 to 0.200 g/l, calculated as H_2O_2 .

- 33. (previously presented) The process according to claim 20, wherein the content of magnesium in the phosphating solution is not more than 1 g/l.
- 34. (previously presented) The process according to claim 33, wherein the contents of the magnesium is not more than 0.15 g/l.
- 35. (previously presented) The process according to claim 20, wherein the pH is in the range of 2 to 4.
- 36. (previously presented) The process according to claim 20, wherein the content of free acid determined with KCl is in the range of 0.3 to 6 points, the content of dilute total acid is

in the range of 8 to 70 points or the content of total acid according to Fischer is in the range of 4 to 50 points.

- 37. (previously presented) The process according to claim 20, wherein the phosphate coating is applied at a temperature of from 20 to 70°C.
- 38. (previously presented) The process of claim 20, wherein the surface is a body part for an automobile or an aircraft, a sheet, a wire mesh, or a small plant. plant
 - 29. (new) A process comprising:

applying an aqueous, acidic solution comprising dissolved contents to a metallic surface, said metallic surface comprising at least 5% by weight of at least one of aluminum or an aluminum alloy, wherein the dissolved contents in the phosphating solution comprise:

virtually no sodium or a concentration of sodium in the range of at least 0.04 g/l, virtually no potassium or a concentration of potassium in the range of at least 0.025 g/l, wherein the concentrations of sodium and potassium together is in the range of 0.3 to 1.8 g/l as sodium, the potassium content being converted to sodium on a molar basis; zinc in a concentration range of 0.2 to 4 g/l; phosphate in a concentration range of 4 to 65 g/l, calculated as PO₄; free fluoride in a concentration range of 0.03 to 0.5 gl; total fluoride in the concentration range of 0.1 to 5 g/l;

wherein no or almost no precipitation product based on aluminum fluorocomplexes of ammonium, alkali metal or alkaline-earth metal is deposited on said metallic surface, below the phosphate film and/or between the zinc phosphate crystals in the phosphate film on the surfaces of aluminum or at least one aluminum alloy phosphated in this way and wherein a zinc-

containing phosphate film is deposited on the metallic surfaces and has a coating weight in the range of 0.5 to 10 g/m², wherein the range of free acid is from 0.1 to 0.25 g/L.

30. (new) The process of claims 29, wherein the content of at least one complex flouride is at least $0.5~\rm g/L$.